



Form PTO 1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY DOCKET NO.	SERIAL NO.
		243339US3	10/673,173
		APPLICANT	
		Yukihiko NAKATA, et al.	
LIST OF REFERENCES CITED BY APPLICANT		FILING DATE	GROUP
		September 30, 2003	1753

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
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	AL						
	AM						
	AN						

FOREIGN PATENT DOCUMENTS					
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO
	AO				
	AP				
	AQ				
	AR				
	AS				
	AT				
	AU				

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)		
	AV	Y. NAKATA, et al., Proceedings of Int. Conf. on Rapid Thermal Proceeding for Future Semiconductor Device, 2 pages, "RAPID-LOW-TEMPERATURE PHOTO-OXIDATION PROCESSING FOR ADVANCED POLY-SI TFTS", 2001
	AW	Y. NAKATA, et al., Extended Abstracts of International Workshop on Gate Insulator, pages 120-123, "PHOTO-OXIDATION AND PECVD STACKED GATE INSULATOR FOR POLY-SI TFTS AT 200-300 °C", November 1-2, 2001
	AX	Y. NAKATA, et al., Asia Display/DW '01, pages 376-378, "LOW-TEMPERATURE GATE INSULATOR FOR POLY-SI TFTS BY COMBINATION OF PHOTO OXIDATION AND PECVD", October 16-19, 2001
RRB	AY	Y. NAKATA, et al., Spring 48 <sup>th</sup> Applied Physics Related Joint Lecture Meeting, page 89, "LOW-TEMPERATURE OXIDE FORMATION FOR POLY-SI TFT BY PLASMA AND LIGHT PROCESS", 2001
	AZ	Y. NAKATA, et al., IEICE Transactions on Electronics, vol. E85-C, no. 11, pages 1849-1853, "LOW-TEMPERATURE GATE INSULATOR FOR POLY-SI THIN FILM TRANSISTORS BY COMBINATION OF PHOTO-OXIDATION AND PLASMA ENHANCED CHEMICAL VAPOR DEPOSITION USING TETRAETHYLOTHOSILICATE AND O <sub>2</sub> GASES", November 2002
		<input type="checkbox"/> Additional References sheet(s) attached

Examiner	R Buhl	Date Considered	2-2006
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.			